

WEST[Help](#)[Logout](#)[Interrupt](#)[Main Menu](#) | [Search Form](#) | [Posting Counts](#) | [Show S Numbers](#) | [Edit S Numbers](#) | [Preferences](#)**Search Results -****Terms****Documents**

plasma and clean and etch and ("c.sub.3 f.sub.6" or hexafluoropropylene)

0

Database:

- [US Patents Full-Text Database](#)
- [US Pre-Grant Publication Full-Text Database](#)
- [JPO Abstracts Database](#)
- [EPO Abstracts Database](#)
- [Derwent World Patents Index](#)
- [IBM Technical Disclosure Bulletins](#)

Refine Search:plasma and clean and etch and ("c.sub.3
f.sub.6" or hexafluoropropylene)[Clear](#)**Search History****Today's Date: 10/2/2001**

<u>DB Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
JPAB,EPAB	plasma and clean and etch and ("c.sub.3 f.sub.6" or hexafluoropropylene)	0	<u>L5</u>
USPT	plasma and clean and etch and ("c.sub.3 f.sub.6" or hexafluoropropylene)	25	<u>L4</u>
USPT	l1 and plasma and clean and etch and ("c.sub.3 f.sub.6" or hexafluoropropylene)	1	<u>L3</u>
USPT	l1 and plasma and clean and etch and "c.sub.3 f.sub.6"	0	<u>L2</u>
USPT	((134/\$)!([CCLS])))	26260	<u>L1</u>